

## EFFECT OF ION IMPLANTATION ON THE OXYGEN OVERPOTENTIAL OF Ni ANODES

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This work investigates the use of ion implantation for decreasing the oxygen-overpotential of nickel anodes. It is part of a search for improved electrocatalysts to increase the energy efficiency of the  $H_2O$  electrolysis process for producing  $H_2$  gas.

A series of Ni electrodes were implanted at room temperature with various doses of 50 keV  $Ag^+$ ,  $Li^+$ ,  $He^+$ , or  $Ks^+$  ions. Polarization measurements were then made in a suitable electrolysis cell over a wide range of current densities, using aqueous KOH solution (30%) at  $80^\circ C$  as electrolyte. In the case of  $Ag^+$  implants, Rutherford backscattering (RBS) measurements were performed before and after electrolysis in order to monitor the amount and depth distribution of the Ag atoms.

For  $Li^+$  or  $He^+$  implantation, we observe a negligible change in the measured polarization curves. For high dose  $Kr^+$  implants ( $10^{18}$  ions  $cm^{-2}$ ) the Ni electrode exhibits an increase in overpotential, indicating that excessive damage and/or sputtering of the surface causes some deterioration in electrode behaviour.

For  $Ag^+$  implants, on the other hand, we observe a large (20-40%) reduction in the total overpotential at implant doses of  $0.3-4 \times 10^{16}$   $Ag^+$   $cm^{-2}$ . Furthermore, RBS measurements show that prolonged electrolysis at higher current density (24-28 h at  $1 A/cm^2$ ) produces only a small loss of Ag and shifts its depth profile to significantly larger depths. Supplementary nuclear microanalysis, using the  $^{16}O(d,p)^{17}O$  reaction, show that the shift in Ag profile is correlated with the growth of an anodic nickel oxide (+carbon) layer during electrolysis.

In one set of runs, the Ni electrode were thermally oxidized before  $Ag^+$  implantation in order to form an  $\sim 400$  Å layer of NiO at the surface. In this case, we observe a somewhat smaller reduction in overpotential following  $Ag^+$  implantation; furthermore, a large loss of Ag into the electrolyte occurs during the subsequent electrolysis.

### 1. Introduction

Electrolysis of water is potentially a reversible process, but electrode polarization especially at the oxygen anode increases the required voltage sufficiently to prevent the technological development of high efficiency electrolyzers and fuel cells. Most commercial electrolyzers and fuel cells. Most commercial electrolyzers consist of Ni electrodes immersed in a hot 25-50 wt% KOH electrolyte, but they operate at relatively low voltage efficiencies. Many other metals—for example, Pt, Ru and Ag—would offer superior electrocatalytic performance to Ni, but these are generally too expensive for large scale commercial use. In this regard, ion implantation (or ion-beam-induced mixing) several potential advantages:

(i) the noble metal can be introduced into the near surface region (typically  $<1000$  Å) to a precise and controlled concentration;

(ii) solid solubilities do not limit the maximum achievable concentration;

(iii) because only very near surface layers are being modified, the amount of noble metal can be minimized.

Several years ago, Grenness and Thompson [1] implanted Pt into tungsten and found that the electrocatalytic activity of the surface approached that of platinum itself, even though only a minute amount of platinum had been implanted. A similar study by Rabette et al., [2] examined the catalytic activity of single crystal supports of  $\alpha-Al_2O_3$  and MgO implanted with platinum ions. Also, in a closely related series of studies, Dearnaley [3] and others have demonstrated the value of ion implantation in producing improved corrosion resistance for various metals.

In the present investigation, we have implanted selected species ( $Li^+$  and  $Ag^+$ ) into Ni and oxidized Ni anodes and have measured the resulting change in voltage efficiency as a function of electrolysis current in a suitable  $H_2O$ -electrolysis cell. In the case of the  $Ag^+$  implants, Rutherford backscattering (RBS) and nuclear microanalysis (NMA) have been used to monitor the Ag profile and the oxygen content of the

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anode before and after prolonged electrolysis. Eventually, we hope to extend our investigation to include Pt implantation, but we do not yet have available the necessary ion source for producing  $\mu\text{A}$  beams of  $\text{Pt}^+$ . Some high-dose inert gas ( $\text{He}^+$  and  $\text{Kr}^+$ ) implants have also been studied in order to determine the possible contribution of radiation damage effects.

## 2. Experimental

Our 3-compartment electrolysis cell is shown in fig. 1. The main cell contains the hot (30 wt% KOH) electrolyte and the implanted Ni anode A (embedded in teflon) plus a Pt reference anode,  $A_{\text{ref}}$ ; it is equipped with a cover to minimize evaporation loss.

The main *variable* electrolysis current flows between A and the platinum cathode C which is mounted in a separate compartment to minimize mixing of electrolysis products. A much smaller *constant* current of 1 mA flows between a pair of Pt reference electrodes,  $A_{\text{ref}}$  and  $C_{\text{ref}}$ , with  $C_{\text{ref}}$  also mounted in a separate compartment with only a 2 mm connecting capillary to the main cell.

We measure the potential  $V_1$  between the nickel anode A and the Pt reference cathode  $C_{\text{ref}}$ . At the same time, we also measure the potential  $V_2$  between  $C_{\text{ref}}$  and a reversible  $\text{Pt}(\text{H}_2)$  standard electrode, R. This (dynamic cathode) potential is always quite small — i.e.  $\sim 0.040 \text{ V}$  — and hence the observed variations in  $V_1$  are mainly due to overvoltage effects at or near the Ni anode. Note that  $V_1$  will include some contribution from the ( $iR$ ) voltage drop in the electrolyte near the anode. However, this is not a serious complication in the present work, since our

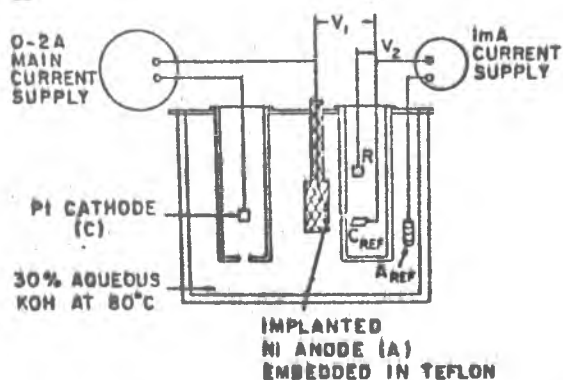


Fig. 1. Schematic diagram of the 3-compartment electrolysis cell.

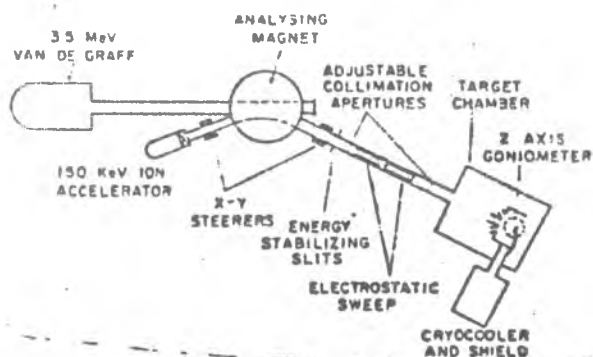


Fig. 2. Ion implantation and RBS analysis facility.

initial objective is only to identify promising implantation systems which can then be investigated more rigorously.

The Ni anodes consisted of 9 mm diameter metal discs, mechanically polished with successively finer metallurgical paper and finally with  $1 \mu\text{m}$  diamond paste. After implantation, the anode was sealed into its teflon holder with a suitable epoxy in order to define reproducibly the effective surface area during electrolysis.

Fig. 2 shows schematically the ion implantation facility at McMaster. The 150 kV accelerator is used for implanting the various ions, and the 3.5 MV Van de Graaff is used for subsequent RBS analyses of the amount and depth profile of  $\text{Ag}^+$  in the implanted electrode. Most of the  $\text{Ag}^+$  implants and also the nuclear microanalyses were carried out at CRNL. All implants were carried out at 300 K and  $\sim 0.5 \mu\text{A cm}^{-2}$ . Note that a cryoshield at  $\sim 30 \text{ K}$  surrounds the target in order to maintain ultra-clean vacuum conditions during both the implantation and the RBS analysis.

For the lightest ions ( $\text{He}^+$  and  $\text{Li}^+$ ), where the implant depth is quite large, each implant involved several different energies in order to obtain a relatively uniform depth distribution.

## 3. Results and discussion

### 3.1. Overpotential measurements

Table 1 summarizes the observed effects of implantation on the oxygen overpotential  $\eta$  of the Ni anode. Of the four implanted species studied to date,  $\text{Ag}^+$  produced a significant reduction in  $\eta$ , especially

Table 1  
Electrochemical behavior of implanted Ni anodes

Implanted species	Reason for selection	Implant energy (keV)	Implant dose (ions cm <sup>-2</sup> )	Observed effect on $\eta$
Li <sup>+</sup>	Li-Ni alloys give improved oxide conductivity and anode performance	15 + 40	10 <sup>15</sup> -10 <sup>16</sup>	nil
<sup>4</sup> He <sup>+</sup> Kr <sup>+</sup>	to investigate the possible influence of bombardment-induced damage or sputtering effects	15 + 40	10 <sup>16</sup> -10 <sup>17</sup>	nil
		12	~10 <sup>18</sup>	small increase
Ag <sup>+</sup>	noble metals (Pt, Ru, etc) are known to be much better anodes than Ni	50	0.3-4.0 x 10 <sup>16</sup>	20-40% reduction

at large values of the current density (i.e.  $i \geq 0.1$  A cm<sup>-2</sup>)—as seen in fig. 3. The other ions all had a negligible effect on  $\eta$ , except Kr<sup>+</sup> which (at much higher dose) actually produced a small increase in  $\eta$ .

Our observed curves of  $\eta$  vs. current density for Ag<sup>+</sup>-implanted anodes appear to be independent of

the implant dose (table 2) over the range 0.3-1.3 X 10<sup>16</sup> Ag<sup>+</sup> cm<sup>-2</sup>, but at the highest dose used (4 X 10<sup>16</sup> cm<sup>-2</sup>) a somewhat larger value of  $\eta$  is obtained. Also, the Ag<sup>+</sup>-implanted Ni-NiO anode shows a smaller improvement than a Ni anode with the same Ag<sup>+</sup> implant dose. As discussed later (fig. 6), this dif-

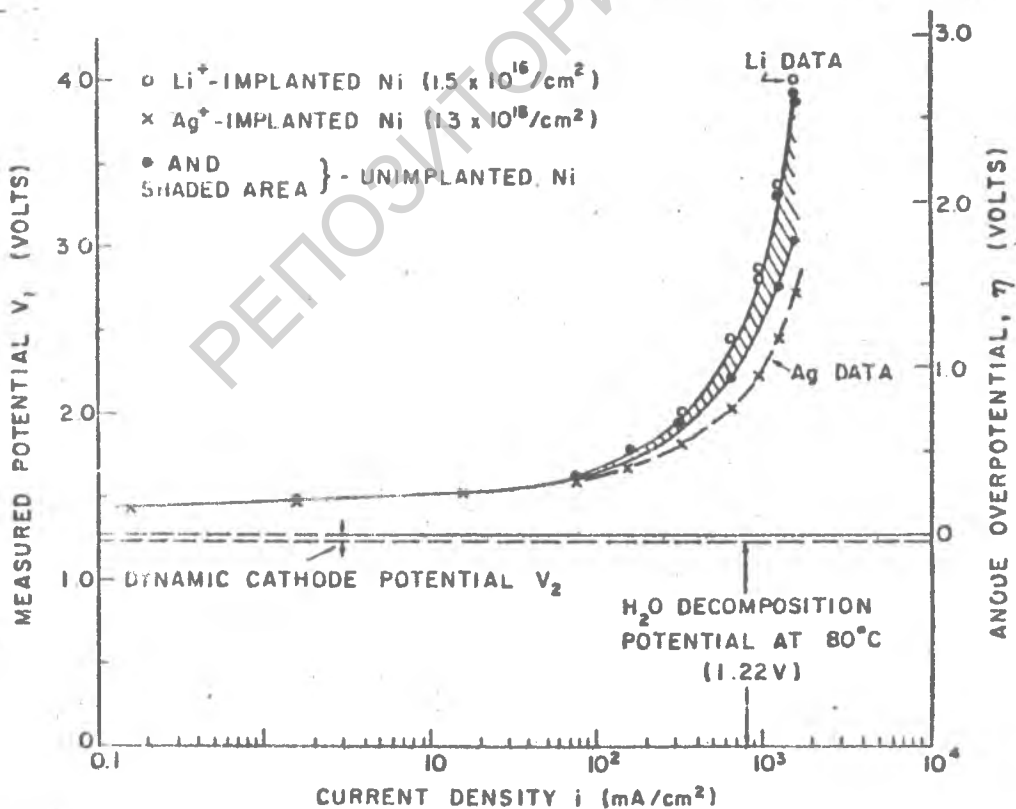


Fig. 3. Tafel plot of the observed potential  $V_1$  vs.  $\log i$  for Ag<sup>+</sup>(+), Li<sup>+</sup>(o) and unimplanted (shaded region) Ni anodes. The corresponding overpotential ( $\eta$ ) values are shown on the right hand scale.

Table 2  
Overpotential  $\eta$  of  $\text{Ag}^+$ -implanted Ni at  $1 \text{ A cm}^{-2}$

Target	Implant ( $10^{16} \text{ Ag}^+ \text{ cm}^{-2}$ )	$\eta$ (V)
Ni	0.3	0.94
	0.6	0.99
	1.3	0.94
	4.0	1.14
NiO	1.3	1.24
Unimplanted Ni		1.3–1.6

ference is probably associated with the large loss of Ag during electrolysis in the pre-oxidized Ni–NiO case.

One rather troublesome feature of the unimplanted Ni anodes was a rather large variation in the observed overpotential from sample to sample—as shown by the shaded area in fig. 3. The  $\text{Ag}^+$ -implanted anodes, on the other hand, gave much more reproducible  $\eta$  vs.  $\log i$  curves. A similar but less dramatic improvement in reproducibility was also seen in the  $\text{Li}^+$  and even in the  $\text{He}^+$  implants. Microscopic examination of these implanted anode surfaces

after prolonged electrolysis show a much more uniform corrosion film than on an unimplanted sample. Similarly, anodes which had been pre-oxidized to form an  $\sim 400 \text{ \AA}$  surface NiO layer also exhibit much better reproducibility during electrolysis than the untreated Ni anodes—and a more uniform corrosion film.

The inert gas implants ( $\text{He}^+$  and  $\text{Kr}^+$ ), at comparable doses to those used in the  $\text{Ag}^+$  study, show no detectable change in  $\eta$ —indicating that radiation damage effects are not playing a significant role in the observed  $\eta$  reduction. Indeed, at considerably higher dose (i.e.  $\sim 10^{18}$  ions  $\text{cm}^{-2}$ ), the Kr-implanted anodes actually exhibit a small increase in  $\eta$ .

In the case of the  $\text{Li}^+$  implants, the lack of a significant  $\eta$  reduction (table 1) is somewhat surprising, since it was already known [4] that the incorporation of  $\sim 10\%$   $\text{Li}_2\text{O}$  into the oxidized surface of a Ni anode produces a marked increase in oxide conductivity and a consequent reduction in overpotential.

At  $i$  values  $\leq 0.1 \text{ A cm}^{-2}$ , our measured values of  $V_1$  (and hence  $\eta$ ) exhibit an approximately linear dependence on  $\log i$ , with the slope of this Tafel plot (fig. 3) being typically  $\sim 0.05 \text{ V}$ . At higher  $i$  values, however,  $V_1$  increases much more rapidly and eventually approaches an almost linear dependence on  $i$  (fig. 4) indicating that the ( $iR$ ) drop in the electrolyte

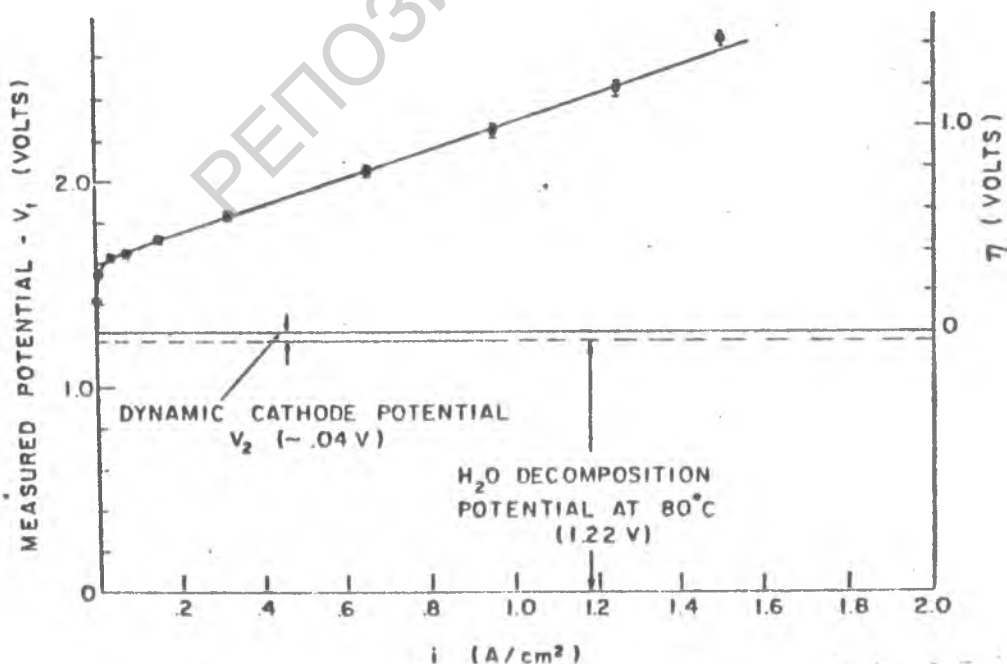


Fig. 4. Observed potential  $V_1$  as a function of  $i$  for a  $\text{Ag}^+$ -implanted Ni anode ( $1.3 \times 10^{16} \text{ Ag cm}^{-2}$  at 50 keV).

near the anode is now starting to make a significant contribution to the  $V_1$  measurements. Obviously, in future work, a more extensive potential-measuring technique will be required to distinguish the relative contribution of  $\eta$  and  $(iR)$  drop to  $V_1$ .

### 3.2. Anode discharge potential

After each Ni anode had been subjected to a 24 h electrolysis run, the current was turned off and the residual discharge potential was monitored for several hours. The  $\text{Ag}^+$ -implanted anodes exhibit a well-defined plateau at  $\sim 1.3$  V (fig. 5) before dropping to the normal steady-state value of 0.9 V. It is interesting to note that the length of this plateau increases linearly with  $\text{Ag}^+$  implant dose and, from the known impedance of the recording voltmeter ( $1 \times 10^6 \Omega$ ), we estimate that the integrated charge flowing during this plateau "phase" is equivalent roughly to two electrons per implanted Ag atom. This would suggest the formation, during electrolysis, of an intermediate complex involving the storage of  $\sim$ one oxygen ion per implanted Ag atom. Note that the unimplanted Ni anode exhibits no well-defined plateau at all.

### 3.3. Rutherford backscattering (RBS) and nuclear microanalysis (NMA)

Before and after electrolysis, each of the  $\text{Ag}^+$ -implanted anodes was analysed by RBS, using a beam of 2.0 MeV  $^4\text{He}^+$  ions. The results obtained on the  $3 \times 10^{16}$  atoms  $\text{cm}^{-2}$  implant are shown in fig. 6. The initial Ag peak position is seen to occur just slightly deeper than the predicted  $R_{\text{LSS}}$  implant depth. After the first 24 h electrolysis run at  $\sim 1$  A  $\text{cm}^{-2}$ , the Ag peak is shifted  $\sim 200$  Å deeper into the Ni, but its total area remains unchanged indicating that negligible loss of Ag has occurred.

Nuclear microanalysis, using 970 keV deuterons and the  $^{16}\text{O}(d,p)^{17}\text{O}$  reaction, shows that the Ni anode had picked up  $\sim 2 \times 10^{17}$  oxygen atoms  $\text{cm}^{-2}$  during this first 24 h electrolysis; this is equivalent to the formation of  $\sim 400$  Å of NiO on the anode surface. Trapping of Ag at this mobile Ni-NiO interface could well explain the observed Ag peak shift in fig. 6. Simultaneous observation of the  $^{12}\text{C}(d,p)^{13}\text{C}$  reaction yield shows that the surface "oxide layer" also contains a comparable number ( $\sim 1.5 \times 10^{17}$   $\text{cm}^{-2}$ ) of carbon atoms and hence is more complex a molecular structure than NiO.

Further electrolyses for additional 24 h periods

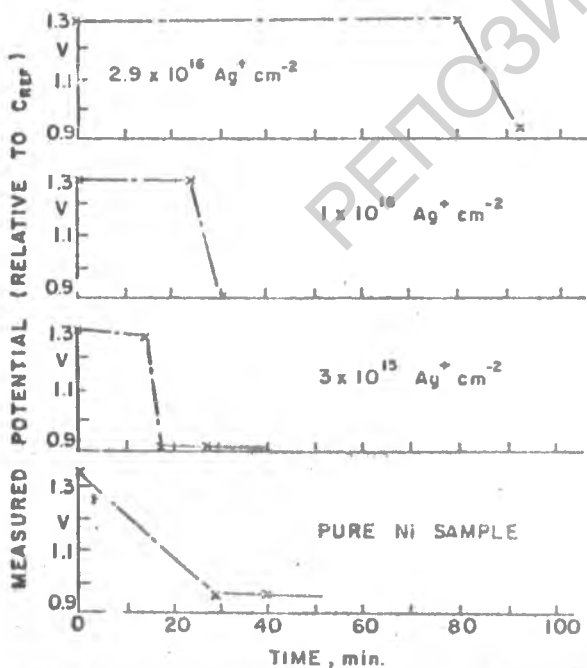


Fig. 5. Anode discharge potential ( $V_1$ ) with the electrolysis current turned off.

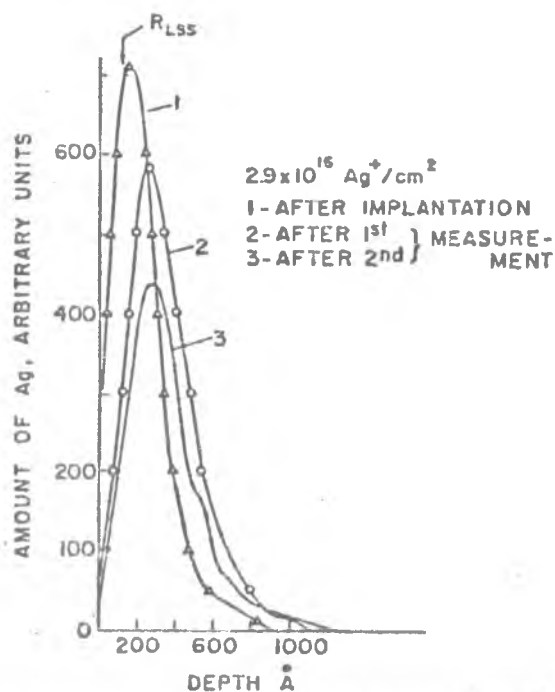


Fig. 6. RBS measurement of the implanted Ag profile in Ni before and after 24 h electrolysis runs.

produce no further shift in the Ag peak position, but a gradual reduction in area occurs, indicating a gradual loss of Ag into the electrolyte.

A similar RBS study of Ag<sup>+</sup> implanted into pre-oxidized Ni anodes (400 Å NiO) shows no change in the Ag peak position but >50% loss to the electrolyte during the first 24 h electrolysis period. The poorer electrolytic performance of the implanted Ni–NiO anode (table 2) is probable related to this large loss of Ag into the electrolyte.

#### 4. Conclusions

A very significant reduction in the anodic overpotential of nickel can be obtained by Ag<sup>+</sup> implantation at  $\sim 1 \times 10^{16}$  atoms  $\text{cm}^{-2}$ , but more extensive electrochemical studies will be required to establish the relative contributions of oxygen overvoltage and electrolyte resistivity.

During electrolysis, the implanted Ag profile is swept several hundred Å deeper into the Ni, probably by trapping at the moving Ni–NiO interface.

Inert gas (He<sup>+</sup>, Kr<sup>+</sup>) and Li<sup>+</sup> implantations have negligible effect at  $10^{15}$ – $10^{16}$  atoms  $\text{cm}^{-2}$  implant doses.

We are especially grateful to Orville Westcott at CRNL for providing the Ag implantations.

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